

L Number	Hits	Search Text	DB	Time stamp
1	8682	(250/311,306,307,310,396R,397-399,396,491.1	USPAT;1,492.22,492.3).ccls.	2004/11/03 09:35
2	0	((250/311,306,307,310,396R,397-399,396,491.1	US-PGPUB	2004/11/03 09:36
3	270	and ((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or	DERWENT; IBM_TDB	2004/11/03 09:37
4	326	((250/311,306,307,310,396R,397-399,396,491.1	USPAT;1,492.22,492.3).ccls.	2004/11/03 09:37
5	326	and ((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or	USPAT; US-PGPUB	2004/11/03 09:37
6	0	((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and ((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or	EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:39
7	0	((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and ((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or	EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:39
8	0	((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and ((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or	EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:39
9	0	((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and ((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or	EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:40
10	0	((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and ((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or	EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:39
11	1	((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and ((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:39
12	3	((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and ((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:39
13	34	((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and ((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:40

or mask or reticle))) and ((shaped near2 beam) and (reflect\$4 and transmit\$5))

14	36	(((((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or ((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and (((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) and ((shaped near2 beam) with (multi\$5 adj beam))) or (((((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or ((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and (((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) and ((shaped near2 beam) and (multiple adj beam))) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:40
15	1	(((((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or ((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and (((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) and ((shaped near2 beam) with (multi\$5 adj beam))) or (((((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or ((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and (((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) and ((shaped near2 beam) and (multiple adj beam))) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:45
16	5	(((((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) or ((250/311,306,307,310,396R,397-399,396,491.1,492.1,492.22,492.3).ccls.) and (((charged adj particle) or electron) near2 beam) and (inspect\$5 near2 (wafer or mask or reticle))) and ((shaped near2 beam) and (multiple adj beam))) or	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:44
17	1	6184526.pn. and (((cross adj1 sectional) near2 shape\$2) with (triang\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:44
18	1	6184526.pn. and (((cross adj1 sectional) near2 shape\$2) with (triang\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:53
19	0	6184526.pn. and (((cross adj1 sectional) near2 shape\$2) with (triang\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:49
21	0	6184526.pn. and (((multi\$3 adj2 apertur\$3) near3 array\$2) with mask\$2)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:53
22	0	6184526.pn. and (multi\$3 adj2 apertur\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/11/03 09:53